

What is claimed is:

1. A color filter substrate for a display device, comprising:
a base substrate having a transmissive portion and a reflective portion, the
transmissive portion having a groove;
5 a black matrix on the base substrate; and
a color filter layer on the black matrix and on the base substrate.
2. The color filter substrate according to claim 1, wherein the base
substrate is made of transparent plastic.
3. The color filter substrate according to claim 2, wherein the groove is
formed by molding.
4. A color filter substrate for a display device, comprising:
15 a base substrate having a transmissive portion and a reflective portion, the
transmissive portion having a groove;
a color filter layer on the base substrate; and
a black matrix on the color filter layer.
5. A method of fabricating a color filter substrate for a display device,
comprising:
forming a groove on a base substrate, the base substrate having a transmissive
portion and a reflective portion, the transmissive portion having the groove;
forming a black matrix on the base substrate; and

forming a color filter layer of a first color on the black matrix and the base substrate.

6. The method according to claim 5, further comprising:

forming color filter layers of second and third colors on the black matrix and on the base substrate.

7. The method according to claim 5, wherein the groove is formed by selectively etching the base substrate.

8. The method according to claim 5, wherein the base substrate is made of transparent plastic.

9. The method according to claim 8, wherein the groove is formed by molding.

10. A method of fabricating a color filter substrate for a display device, comprising:

forming an opaque metal pattern on a base substrate, the base substrate having a transmissive portion and a reflective portion, the opaque metal pattern being formed at the reflective portion;

forming a groove at the transmissive portion by selectively removing the base substrate using the opaque metal pattern as a mask;

forming a black matrix on the base substrate by selectively removing the opaque metal pattern; and

forming a color filter layer of a first color on the black matrix and on the base substrate.

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11. The method according to claim 10, further comprising:

forming color filter layers of second and third colors on the black matrix and on the base substrate.

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12. A color filter substrate for a display device, comprising:

a base substrate having a transmissive portion and a reflective portion;

a black matrix on the base substrate;

a plurality of buffer patterns at the reflective portion, the plurality of buffer patterns having a substantially uneven shape; and

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a color filter layer at the transmissive and reflective portions.

13. The color filter substrate according to claim 12, wherein the color filter layer at the transmissive portion is thicker than that at the reflective portion.

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14. The color filter substrate according to claim 12, wherein the plurality of buffer patterns are formed by selectively removing the base substrate.

15. The color filter substrate according to claim 14, wherein the base substrate is made of glass.

16. The color filter substrate according to claim 12, wherein the plurality of buffer patterns are formed by depositing and selectively removing a transparent material.

5 17. The color filter substrate according to claim 16, wherein the plurality of buffer patterns are formed of one of benzocyclobutene, acrylic resin and silicon nitride.

18. The color filter substrate according to claim 12, wherein the plurality of buffer patterns have a uniform pitch.

10 19. The color filter substrate according to claim 18, wherein the pitch is within a range of about 14 to 45 micrometers.

20. The color filter substrate according to claim 12, wherein a bottom
15 surface of the plurality of the buffer patterns is located higher than a top surface of the transmissive portion of the base substrate.

21. A method of fabricating a color filter substrate for a liquid crystal display device, comprising:

20 forming a black matrix on a base substrate, the base substrate having a transmissive portion and a reflective portion;

forming a plurality of buffer patterns at the transmissive portion, the plurality of buffer patterns having a substantially uneven shape; and

forming a color filter layer at the transmissive and reflective portions.

22. The method according to claim 21, wherein the plurality of buffer patterns have a uniform pitch.

23. The method according to claim 22, wherein the pitch is within a range of about 14 to 45 micrometers.

24. The method according to claim 21, wherein a bottom surface of the plurality of the buffer patterns is located higher than a top surface of the transmissive portion of the base substrate.

25. The method according to claim 21, wherein the plurality of buffer patterns are formed by depositing and selectively removing a transparent material.

26. The method according to claim 25, wherein the plurality of buffer patterns are formed of one of benzocyclobutene, acrylic resin and silicon nitride.

27. A method of fabricating a color filter substrate for a display device, comprising:

forming a plurality of buffer patterns by selectively etching a base substrate, the base substrate having a transmissive portion and a reflective portion, the plurality of buffer patterns being formed at the reflective portion and having a substantially uneven shape;

forming a black matrix on the plurality of the buffer patterns; and

forming a color filter layer at the transmissive and reflective portions.

28. The method according to claim 27, wherein the plurality of buffer patterns have a uniform pitch.

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29. The method according to claim 28, wherein the pitch is within a range of about 14 to 45 micrometers.

30. The method according to claim 27, further comprising:
forming an opaque metal pattern on the base substrate.

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31. The method according to claim 27, wherein the base substrate is made of glass.

32. The method according to claim 27, wherein a bottom surface of the plurality of the buffer patterns is located higher than a top surface of the transmissive portion of the base substrate.

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33. The method according to claim 32, further comprising:
etching only the transmissive portion of the base substrate.

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34. A method of fabricating a color filter substrate for a display device, comprising:

forming an opaque metal pattern on a base substrate, the base substrate having a transmissive portion and a reflective portion, the opaque metal pattern being formed at the reflective portion;

forming a plurality of buffer patterns at the reflective portion by selectively
5 removing the base substrate using the opaque metal pattern as a mask;

forming a black matrix on the base substrate by selectively removing the opaque metal pattern; and

forming a color filter layer at the transmissive and reflective portions.